



# DEPFET detectors for future e<sup>+</sup>e<sup>-</sup> colliders

Carlos Marinas University of Bonn

On behalf of the DEPFET Collaboration



cmarinas@uni-bonn.de

### Outline



### SuperKEKB and ILC

- Common requirements
- DEPFET system
  - Sensor development
  - ASICs
- Latest results
  - Lab and beam tests

### **The ILD vertex detector**



#### The Belle II Collaboration decided on DEPFET as baseline for the pixel detector



1			
	L	P	

	ILD LOI 5-layer layout	Belle II	
Radii	15, 26, 38, 49, 60	14, 22	mm
Ladder length	123 (L1), 250 (L2-L5)	90 (L1), 122 (L2)	mm
Sensitive width	13 (L1), 22 (L2-L5)	12.5 (L1-L2)	mm
Number of ladders	8, 8, 12, 16, 20	8, 12	
Pixel size	25x25 (L1-L5)	50x50 (L1), 50x75 (L2)	μm²
Frame rate	20 (L1), 4 (L2-L5)	50	kHz

The Belle II PXD DEPFET ladders: *almost* prototypes for L1 and L2 of ILD



• Both detectors have very similar (challenging!) requirements:

	ILC	Belle II
Single point resolution	<5 µm	<10 µm
Radiation	~1 Mrad (10 years)	~20 Mrad (10 years)
Material budget	0.1 % X <sub>0</sub> /layer	0.2 % X <sub>0</sub> /layer
Frame time	25-100 µs	20 µs

- High granularity for excellent spatial resolution
- Radiation tolerant to e<sup>-</sup> (X rays) in the MeV (tens keV) range
- Low material budget:
  - Ultra transparent sensors with large SNR.
  - Low power dissipation
  - Minimal support, reduced services, and cooling material
- Fast readout

### The DEPFET ladder





**DHP** (Data Handling Processor) First data compression



IBM CMOS 90 nm (TSMC 65 nm) Size  $4.0 \times 3.2 \text{ mm}^2$ Stores raw data and pedestals Common mode and pedestal correction Data reduction (zero suppression) Timing signal generation Rad. Hard proved (100 Mrad) <sup>5</sup>

### **The DEPFET ladder**



### **Off-module signal flow**







Use anisotropic etching on bonded wafers to create a thin, self-supporting sensor  $\rightarrow$  One material: uniform and small thermal expansion



### **PXD6 DEPFET latest prototype production**





8 SOI wafers with 50  $\mu$ m thin sensors (400  $\mu$ m handle)

- $\bullet$  Small test matrices to test different pixel sizes (50-200  $\mu m)$
- Design variations: short gate lengths, clear structures, drift
- Full size sensors –half ladders for prototyping
- Technology variations on the wafer level

#### 90 steps fabrication process:

- 450 μm 50 μm
- 9 Implantations
  19 Lithographies
  2 Poly-layers
  2 Alu-layers
  1 Copper layer
  Back side processing

## First 50 µm thin DEPFET sensors produced!



cmarinas@uni-bonn.de

### Hybrid 5.0 – Concept demonstrator

universität**bonn** 

- Zero suppressed readout with the minimum necessary amount of components:
  - One Switcher-B
  - One DCDBv2
  - One DHP 0.2
  - Small thin matrix: Belle II SD PXD6 type, 16x128 pixels, 50x75 μm<sup>2</sup> pitch
- Frame rate: 300 kHz (small matrix)







- Data processing
- SWITCHER sequencing
- Inter-chip communication
- Serial link



Photo of the hybrid 5 (without DEPFET matrix)

Un-triggered acquisition, DHP0.2 data loss characteristic as a function of the input data occupancy (C++ and real chip)



No data loss for the expected occupancy

### Laboratory tests: DHP



- Data processing
- SWITCHER sequencing
- Inter-chip communication
- Serial link





Photo of the hybrid 5 (without DEPFET matrix)



DHP can control the SwitcherB sequence

### Laboratory tests: DHP

- Data processing
- SWITCHER sequencing

Photo of the hybrid 5 (without DEPFET matrix)

- Inter-chip communication
- Serial link



150 -







## DCDB and DHP can communicate at full speed

### Laboratory tests: DHP



- Data processing
- SWITCHER sequencing
- Inter-chip communication
- Serial link





#### Irradiated (100 Mrad) DHPT 0.1, can drive 15 m of Infiniband cable

### Laboratory tests: DCD



V<sub>gate, off</sub> V DCD dynamic measurements • gate, on Readout speed with single sampling  $\mathsf{V}_{\mathsf{dear},\mathsf{high}}$  $\mathsf{V}_{\mathsf{clear},\mathsf{lov}}$ Belle II PXD frame readout: 20 µs ٠ (50 KHz frame rate) drain integration / Read-clear cycle: 100 ns ۲ readout clear next cycle charge collection (768 rows, 4 fold readout) 15 Enough headroom for safe fast speed operation during clear gate off / clear off 1<sup>st</sup> sample gate on clear on -15 time / ns 90 ns Long drain lines  $\sim 60 \, \text{pF}$  parasitic -20 -10 10 20 30 40 50 60 70 80 90 0 capacitance

### Laboratory tests: DEPFET sensor



- Biasing optimization (HV, ClearGate, Drift)
- Laser scan ٠ Charge collection homogeneity In pixel studies
- Radioactive source • System calibration





Homogeneous charge collection 16

#### **Beam tests**

DEPFET PXD6 extensively tested over the last campaigns 120 GeV pions at CERN-SPS 1-5 GeV electrons at DESY

#### **Sensor properties**

Charge collection homogeneity, operating points, efficiency, angular scans Various pixel sizes, gate lengths, clear structures, drift regions and pixel designs

#### System related aspects

Power supply prototypes DHH and ONSEN readout

#### Here, just an appetizer

cmarinas@uni-bonn.de

### **Beam tests**

universität**bonn** 



### **Beam tests**





Data analysis is ongoing

### TB 2008 and 2009: PXD5 ILC sensors





### **Expected resolution at ILC**





### **Electric MultiChip Module (E-MCM)**





4 layer kapton cable attached and wire bonded to Si-Module for I/O and power

### **Electric MultiChip Module (E-MCM)**





Metal system as close as possible to final  $\rightarrow$  Electrical information



E-MCM in reality

→ Modules produced, tested and ready for flip chip





- ↘ 4-fold readout possible
  - → Two times faster frame readout keeping the row rate

cmarinas@uni-bonn.de

Detail of the Switcher landing area



- The DEPFET Collaboration is developing utra-transparent pixel sensors with integrated amplification
- The good performance of the DEPFET detector system in terms of SNR, spatial resolution, readout speed is demonstrated
- The Belle II PXD boosted the development of DEPFET detectors
   → Direct benefit towards the ILC-VXD project (ILD-VXD layer concept 'engineered')
- Building a real system: Every detail (although not covered here) is being considered

→ Interconnection technologies, rad. Hardness, cooling, mechanics, ... (see backup)

 $\rightarrow$  For more detailed information: "DEPFET active pixel detectors for a future linear e+e- collider". M. Vos *et al.* arXiv:1212.2160





# Thank you



cmarinas@uni-bonn.de

### **Radiation hardness**



Oxide damage at Gates Bulk damage 1.5x10<sup>-4</sup>  $\alpha = 4.08 \times 10^{-19}$  A/cm 4 μm, x-ray 5 μm, x-ray 1.3x10<sup>-4</sup> 6 μm, x-ray Negligible contribution (<400 e-) at Troom - 6 μm DEPFET, e after 10 Mrad (Internal Gate: 40 ke-) 4 1.0x10<sup>-4</sup> AI / V (A/cm<sup>3</sup>) V<sub>th</sub> shift (V) 7.5x10<sup>-5</sup> 10 MeV e 5.0x10<sup>-5</sup>  $y = a + b^*x$ Equation No Weighting Weight 2.18605E-10 Residual Sum of Squares 2.5x10<sup>-5</sup> 5 V at 10 Mrad 0.98955 0 Adj. R-Square Value Standard Error Intercept Deltal/V 2.09495E-20 Slope 4.08259E-19 0.0 0 2000 4000 6000 8000 10000 0.00E+000 1.00E+014 2.00E+014 3.00E+014 Dose (krad) Electron fluence (cm<sup>-2</sup>)

Threshold voltage
 shift can be handled
 by the system

DE+000 1.00E+014 2.00E+014 3.00E+014 4.00E+014 Electron fluence (cm<sup>-2</sup>) Damage constant:  $\alpha_{el}$ =4.2·10<sup>-19</sup> A/cm Damage constant:  $\alpha_n$ =4.0·10<sup>-17</sup> A/cm → Hardness factor is lower than expected  $\kappa_{meas} = \frac{\alpha(10MeVe^{-})}{\alpha(1MeVn)} = 0.014$   $\kappa_{theo} = \frac{NIEL(10MeVe^{-})}{NIEL(1MeVn)} = 0.06$ ✓ Relaxed bulk damage 27

### DCDB



28

Drain Current Digitizer for Belle II

- 512 ADCs
- Cyclic conversion
- 320 MHz clocked
- 100 ns conversion time
- Mean INL < 1.5LSB (Max < 2.2 LSB)
- Gain variation < 5% (peak to peak)





cmarinas@uni-bonn.de



### **DCD Channel Layout**





- ADC Operation
  - 1. Sample input current with two Current Memory Cells (CMC1 and CMC2)
  - 2. Compare Current from one CMC to low/high threshold
  - 3. If above/below low/high threshold, activate add/subtract current sources
  - 4. Copy current from CMC1, CMC2 and extra current sources to CMC3 and CMC4.
  - 5. Repeat from Step 2 (with CMC3 and CMC 4)

### **DHP 0.2**







Data Handling Processor

- Digital common mode subtraction
- Digital pedestal compensation
- Zero suppression
- First full size chip
- Switcher control
- 1.6 Gb serial link
- 3 % occupancy with <1% data loss





 $\rightarrow$  The efficiency is higher, both column and row wise, than 99.5%

### **Building the Belle II PXD**





Inner layer close to the IP (14mm)

Additional carbon fibers capillaries to cool the Switchers, if needed (not tested yet)

### **Measurements with mockup**





### **Thermo-mechanical measurements**





cmarinas@uni-bonn.de

Temperatur [°C]

### ILC scenario: Power cycle and air only



↘ Naïve approach using the XFEL hands-on:

 The power consumptions are weighted accordingly to the estimated duty cycle.
 → Completely shutting down the DEPFET and the analogue part of the electronics between trains → 1/25 power reduction if 1/100 duty cycle



The air speed and temperature are not optimized to minimize the temperature distribution

 $P_{FE}$ =(0.5/25.) W / per chip  $P_{Sw}$ =(0.1/25.) W / per chip  $P_{Sensor}$ =(1./25.) W in total

↘ Although <u>very</u> preliminary, the cooling seems feasible so far

### **Material budget**

universität**bonn** 



	Belle II	ILC
Frame thickness	525 µm	450µm
Sensitive layer	75 μm	50µm
Switcher thickness	500µm	100µm
Cu layer	only on periphery	50% cover over all
Total	0.21 %X0	0.15 %X0

cmarinas@uni-bonn.de

### **ILD 3 double layer VXD option**





- Complementary etch grooves in support frames
- Same process step as thinning and micro-joint (Belle II)
- Adhesive joint between layers



- DEPFET technology is NOT linked only to the 5 layer VXD option
- Single ladder engineered to a large extent
- Double layer still needs R&D